

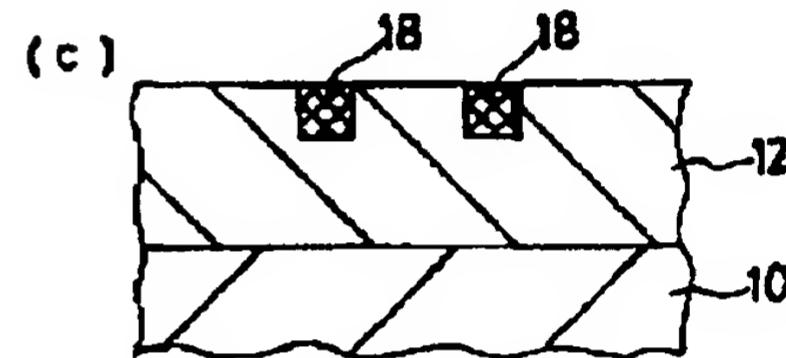
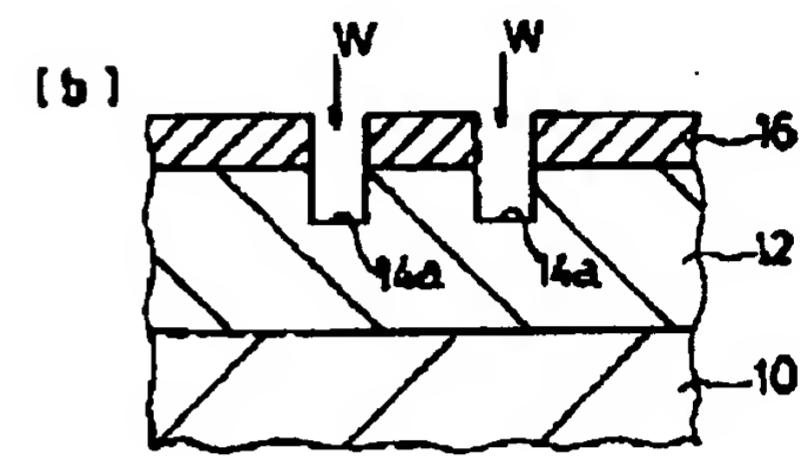
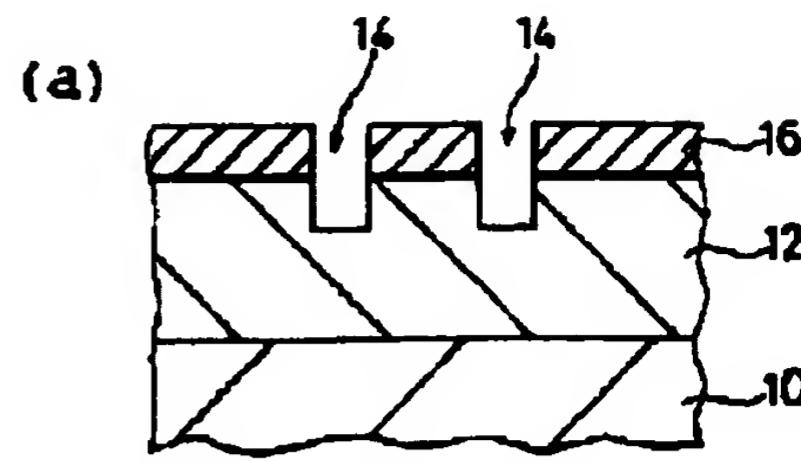
# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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APPLICANT : KAWASAKI STEEL CORP;  
INVENTOR : MIYAMOTO IKUO;  
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TITLE : SEMICONDUCTOR DEVICE AND ITS  
MANUFACTURE



ABSTRACT : PURPOSE: To provide a semiconductor device and its manufacturing method wherein the coverage of a step-difference in a fine device is sufficiently ensured, the wiring formation process can be simplified, and low resistance wiring of high reliability is formed.

CONSTITUTION: By an ion implantation method, W ions are implanted in the bottom part 14a of a wiring trench 14. This ion implantation is performed by using resist 16 as a mask which resist has been stuck at the time of forming the wiring trench 14. As the result, a layer containing W is formed in the bottom part 14a of the wiring trench 14.

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